

**Amendments to the Claims:**

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Previously Presented) A sol in which particles are dispersed in a medium, wherein the particles have a particle size of 50 to 150 nm and comprise as a main component crystalline cerium oxide of the cubic system and as an additional component a lanthanum compound, neodymium compound or a combination thereof, wherein the additional component is contained in  $X/(Ce + X)$  molar ratio of 0.005 to 0.15 in which X is lanthanum atoms, neodymium atoms or a combination thereof.

2. (Original) A sol according to claim 1, wherein the additional component is a lanthanum compound.

3. (Original) A sol according to claim 1, wherein the additional component is a neodymium compound.

4-9. (Canceled)

10. (Previously Presented) An abrasive containing a sol in which particles are dispersed in an aqueous medium in a range of 0.1 to 50 wt%, wherein the particles have a particle size of 50 to 150 nm and comprise as a main component crystalline cerium oxide of the cubic system and as an additional component a lanthanum compound, neodymium compound or a combination thereof, wherein the additional component is contained in  $X/(Ce + X)$  molar ratio of 0.005 to 0.15 in which X is lanthanum atoms, neodymium atoms or a combination thereof.

11. (Withdrawn-Currently Amended) ~~A method of making an abrasive containing a sol in which particles are dispersed in a medium, wherein the particles have a particle size of 50 to 150 nm and comprise as a main component crystalline cerium oxide of the cubic system and as an additional component a lanthanum compound, neodymium~~

~~compound or a combination thereof, wherein the additional component is contained in X/(Ce + X) molar ratio of 0.005 to 0.15 in which X is lanthanum atoms, neodymium atoms or a combination thereof, the method comprising producing~~ An abrasive according to claim 10,  
wherein the sol is produced according to the steps:

a first step of reacting an aqueous solution which a cerium (III) salt is mixed with a lanthanum (III) salt, a neodymium (III) salt or a combination thereof in an aqueous medium in X/(Ce + X) molar ratio of ~~0.001 to 0.5~~ 0.005 to 0.15, with an alkaline substance in (OH<sup>-</sup>)/(Ce<sup>3+</sup> + X<sup>3+</sup>) molar ratio of 3 to 30 to give a suspension in which cerium (III) hydroxide and a hydroxide of the trivalent additional component X are homogeneously mixed; and

a second step of blowing oxygen or a gas containing oxygen into the suspension at a temperature of 10 to 95°C.

12. (Previously Presented) An abrasive according to claim 10, wherein the additional component is a lanthanum compound.

13. (Previously Presented) An abrasive according to claim 10, wherein the additional component is a neodymium compound.

14. (Previously Presented) An abrasive according to claim 10, which is adjusted with an acidic substance to a pH of 1 to 6.

15. (Previously Presented) An abrasive according to claim 10, which is adjusted with a basic substance to a pH of 8 to 13.

16. (Previously Presented) An abrasive according to claim 10, which is used for polishing a substrate which comprises silica as a main component.

17. (Previously Presented) An abrasive according to claim 10, which is used for polishing a rock crystal, a quartz glass for photomask, a semiconductor device or a hard disk made of glass.

18. (Previously Presented) An abrasive according to claim 10, which is used in a step of polishing an organic film, a step of polishing Inter Layer Dielectric (ILD) or a step of shallow trench isolation, for polishing a semiconductor device.